

**WELL-ORDERED MESOPOROUS TITANIA (TMF-108) WITH BRONZE AND ANATASE PHASES AND PROCESS FOR ITS PREPARATION THEREOF**

**IITM Technology Available for Licensing**

**Problem Statement**

- Generally, for synthesizing high quality ordered mesoporous materials, the high reactivity of titania precursor during hydrolysis leads to **uncontrolled phase separation between surfactant template and precursor**, therefore normally results in **disordered framework**.
- Further, preparation of these materials **encounters collapse of ordered mesoporous framework upon removal of the surfactant on calcination**.

**Technology Category/ Market**

**Category – Advance Materials and Manufacturing Applications** –Catalysis, Paints, Diagnostics, Cosmetics Drug Delivery Systems,

**Industry-** Nanotechnology, Chemicals, Manufacturing, Healthcare

**Market** -The global microporous and mesoporous materials market size was **USD 8,601.7million in 2021**. The market is projected to touch **USD 14,930 million** by 2028 exhibiting a **CAGR of 8.2%** during the forecast period.

**Key Features / Value Proposition**

**Technical Perspective:**

- ❑ **Unique combination of anatase and TiO<sub>2</sub>(B) mixed phases having high surface area, wide pore size distribution, and thick pore walls**
- ❑ The **optimum precursor/surfactant ratio** is a key to form thicker pore walls which gives stability to framework and **prevents collapse of mesoporous structure during surfactant removal**.

**User Perspective:**

- ❑ TMF-108 can be used for photocatalytic **dehydrogenation of ethanol** and several other **photocatalytic and photovoltaic application**

**Technology**

- The present invention discloses semiconductor material that includes **preparation of Well-ordered Mesoporous Titania (TMF-108) with Anatase and Titania-B (TiO<sub>2</sub>(B)) mixed phases.**

**METHOD:**

Dissolving 0.274 mmol (4 g) F-108 triblock copolymer in 0.684 mol (40 mL) ethanol and stirring for 2 hours to obtain a homogenous solution



Adding drops of 0.115 mol (16 mL) TiCl<sub>4</sub> (1 M in methylene chloride) under uniform stirring for 2 hours to obtain a clear solution(Molar ratio of TiCl<sub>4</sub>/F108/Ethanol =1:0.0023:5.94)



Pouring the resultant onto petri dish with uniform thickness and solvent is evaporated in an oven (40°C for , 7 days) where inorganic precursor hydrolyses and polymerized into a metal oxide framework



Calcining the resultant at 360°C for 4 h in air at 0.5°C/min to remove the surfactant and obtain **well-ordered mesoporous TiO<sub>2</sub> (TMF-108)**

**Image**

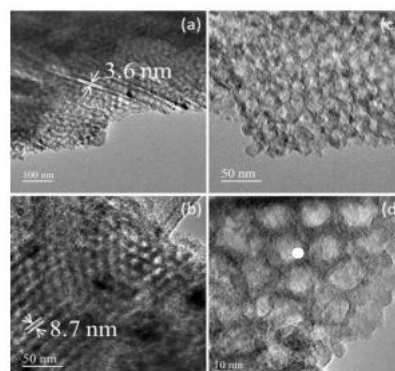


Fig.1(a), (b), (c) and (d) shows SEM images of TMF108

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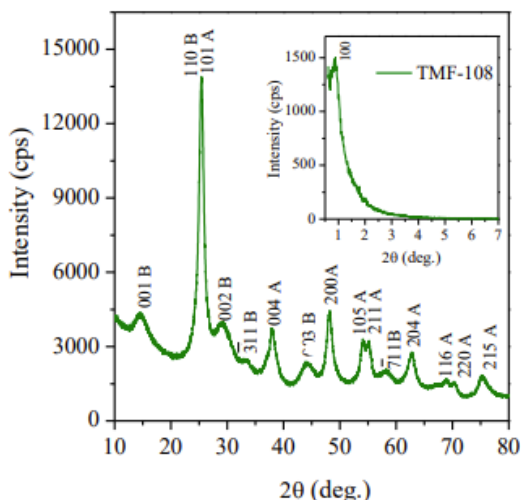
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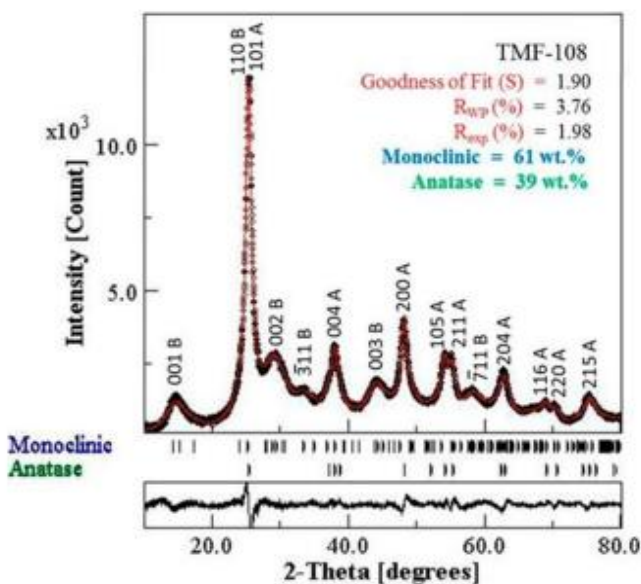
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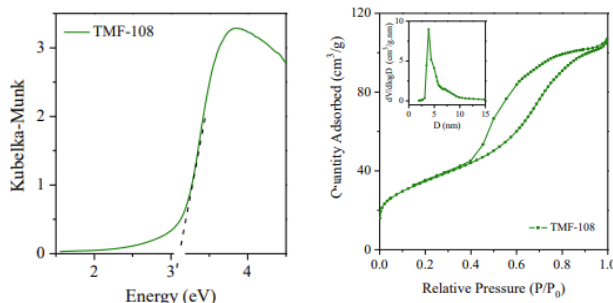
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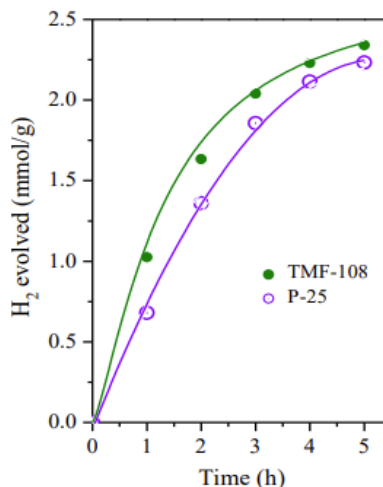
**Fig.2** is the graphical representation of XRD patterns of TMF-108.



**Fig.3** is the graphical representation of Rietveld refined XRD pattern of TMF-108.



**Fig.4** is the graphical representation of Kubelka-Munk plot of TMF-108. **Fig.5** is the graphical representation of N<sub>2</sub> sorption isotherm and pore size distribution (inset) of TMF-108.



**Fig.6** is the graphical representation of Photo-catalytic activity for hydrogen evolution reaction using TMF-108.

### Intellectual Property

- IITM IDF Ref. 1636
- IN377552(Granted)

### TRL (Technology Readiness Level)

TRL- 4, Technology Validated the lab

### Research Lab

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